

ABSTRACT**DYNAMIC SEAL DEPOSITION APPARATUS FOR EPITAXY**

5 The present disclosure provides a dynamic sealing deposition apparatus for epitaxy, relating to the field of semiconductor equipment. The dynamic sealing deposition device for epitaxy comprises a base plate, and a positioning adjustment mechanism is disposed above the base plate. The positioning adjustment mechanism is configured for horizontal positioning adjustment. A lifting and rotating mechanism is provided above the positioning adjustment mechanism. A process chamber is provided above the lifting and rotating mechanism. A holding and ejecting mechanism is provided in the process chamber. The lifting and rotating mechanism is configured for lifting and rotating the holding and ejecting mechanism. The dynamic sealing deposition apparatus for epitaxy solves the technical problems of poor deposition uniformity and poor deposition quality in prior art deposition equipment.

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